編號: 211 國立成功大學 103 學年度碩士班招生考試試題 共 1 頁,第 1 頁 系所組別:電機資訊學院-微電、奈米聯招 考試科目:固態電子元件 考試日期:022,節次:2 ※ 考生請注意:本試題可使用計算機。請於答案卷(卡)作答,於本試題紙上作答者,不予計分。

- 1. If we pack hard spheres in a bcc lattice such that the atom in the center just touches the atoms at the corners
- 1. If we pack hard spheres in a bcc lattice such that the atom in the center just touches the atoms at the corners of the cube, find the fraction of the bcc unit cell volume filled with spheres. (8%)
- 2. Given a semiconductor sample with unknown doping, Hall measurement has been made and the following



information obtained; d = 0.05 cm, $A = d \times W = 1.6 \times 10^{-3}$ cm², I = 2.5 mA, and the magnetic field B is 30 nT (1T = 10^4 Wb/cm²). If a Hall voltage of +10 mV is measured, find the Hall coefficient, conductivity type, majority carrier concentration, resistivity, and mobility of the semiconductor sample. (12%)

- 3. Consider a Si *p-i-n* structure where the *i* region is intrinsic. The doping of *p* region is 10^{15} cm⁻³; the doping of *n* region is 10^{16} cm⁻³. If the lengths of *p*, *i*, *n* region are 2 µm, 1 µm, and 2 µm, respectively, find the depletion layer width for this structure at T = 300 K. (15%)
- 4. An n-channel MOSFET with 10 nm gate oxide thickness has threshold voltages of 0.6 V at $V_{BS} = 0$ V and 0.8 V at $V_{BS} = -1$ V. Find the threshold voltage at $V_{BS} = -2$ V. (15%)
- 5. The capacitances of a metal-*n*-type semiconductor Schottky diode are 10⁻⁷ F/cm at zero bias and 5×10⁻⁸ F/cm at 2 V reverse bias. Find the doping of the n-type semiconductor. (10%)
- 6. Consider a Fabry-Perot laser diode cavity. If N is the number of half-wavelength that can be accommodated in the cavity, please show that the wavelength separation between two adjacent resonant modes is $\Delta \lambda = \lambda^2/2L$, where L is the length of the cavity. (11%)
- 7. Please determine the percentage of light that is absorbed in silicon when the sample is illuminated with a light having the energy hv = 2 eV. Repeat the same calculation for GaAs. The corresponding absorption coefficients (α) of silicon and GaAs are 4×10^3 cm⁻¹ and 1.5×10^4 cm⁻¹, respectively. Both silicon and GaAs are 0.35 µm thick. (11%)
- 8. An optical lithographic system is capable of delivering an exposure power of 0.3 mW/cm². The required exposure energies for a positive and a negative photoresists are 140 mJ/cm² and 9 mJ/cm², respectively. If we could disregard the times needed for loading and unloading wafers, what would be the wafer throughput (in one hour) for both photoresists? (11%)
- 9. If a metal line ($L = 100 \ \mu\text{m}$, $W = 0.18 \ \mu\text{m}$) has a sheet resistance of 25 Ω/sq , what would be the corresponding resistance of the metal line? (7%)